

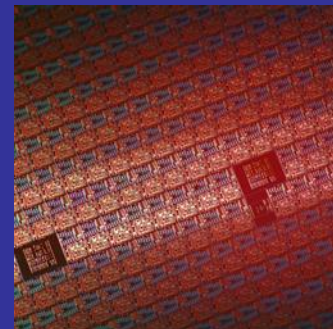


Accelerating the next technology revolution

# Mask Standard Update

*October 6, 2013*

*Long He, John Zimmerman, Ota Kazuya,  
David Halbmaier*







# Pod Standard Revision Adopted: New E152 to Publish Soon



- Line Item #1 – Define Two Rear Purge Port Areas**
- Line Item #2 – Define Two Front Purge Port Areas**
- Line Item #3 – Increase Maximum Component Masses and Define z23 for EUV Pod Specific OHT Flange Height**
- Line Item #4 – Define KC Pin Height z22 and Correct z15 Value**
- Line Item #5 – Define z21 for EUV Pod Latching Position**
- Line Item #6 – Define RFID Terminology and Clarify RFID Location**
- Line Item #7 – Define Eight (8) Outer Carrier Info Pad Configurations**
- Line Item #8 – Correct Values of x4, y5**
- Line Item #9 – Redefining x1 and y1 to Clarify Reticle Position within Inner Pod**

# Mask Standards In Good Shape



-  **New E152 carrier standard to publish soon**
  - All line-items as balloted approved in July
  - New E152 will meet infrastructure needs for next few years
  - Possible pellicle and larger mask would require changes in the scale from major to drastic.
-  **P48 fiducial standard open for revision**
  - Technical solution needed
  - Minimal practical impact to current and near future development activities.
-  **P37 blank standard is current for <math><0.4</math> NA and 6” form factor.**
-  **P40 mask mounting and T16 data matrix fall in background, but sufficient.**